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Form PTO-1449 (Rev. [illegible]) U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No.: 0321.67421	Serial No.: 10/787,070
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Applicant: Andrew B. Kahng et al.	
	Filing Date: February 25, 2004	Group: 2825

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Examiner Initial*		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

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Examiner	James Pan	Date Considered	10-26-05

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